



IDT-1651

SN: 09/838,084

## IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant: Guo-Qiang Lo, et al.

Assignee: Integrated Device Technology, Inc.

Title: DIELECTRIC ANTI-REFLECTIVE COATING SURFACE  
TREATMENT TO PREVENT DEFECT GENERATION IN  
ASSOCIATED WET CLEAN

Serial No: 09/838,084

Group No.: 2823

Filed: 4/18/2001

Examiner: Suk-San Foong

Attorney Docket No.: IDT-1651

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ASSISTANT COMMISSIONER FOR PATENTS  
Washington, D. C. 20231RESPONSE TO FIRST OFFICE ACTION

Sir:

Applicants submit the following remarks and amendments  
in response to the Office Action dated October 22, 2002.

IN THE CLAIMS

Rewrite Claims 1 and 13 as follows.

1. (Amended) A method for preventing the formation of  
watermark defects in a semiconductor process, the method  
comprising:

          patterning a silicon oxynitride layer; then  
          etching a trench in a semiconductor substrate  
through the patterned silicon oxynitride layer; then  
          conditioning the patterned silicon oxynitride  
layer, wherein no wet clean step is performed between  
the etching of the trench and the conditioning of the  
patterned silicon oxynitride layer; and then